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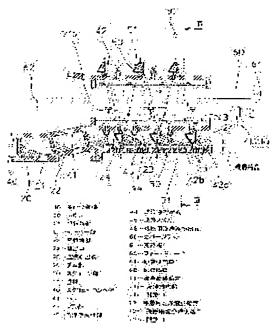
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(54) CENTRIFUGE

(57)Abstract:

PROBLEM TO BE SOLVED: To provide a centrifuge capable of eliminating the lowering of productivity especially accompanying the occurrence of clogging of a screen part as the primary part of a screen bowl centrifuge with a treatment substance such as a crystal or the like and capable of reducing the leak amount of the treatment substance through meshes of the screen part, in the screen bowl centrifuge.

SOLUTION: A washing liquid receiving part 43 for receiving a washing liquid for a washing nozzle 45 is provided in the hub 41 of a screw conveyor 40 while a large number of washing liquid discharge holes 48 for a residual layer arranged at a predetermined interval along the spiral direction of flights 42 are provided in the washing liquid receiving part 43. The washing liquid flying out into a bowl 20 from the washing liquid discharge holes 48 for the residual layer is directly ejected toward a residual layer treatment substance from the fine gaps between the narrow cover flights 50, which extend in the spiral direction along the surfaces 42b on the side opposite to the feed surface 42a for the treatment substance of the flights 42, and the outer peripheral edges of the flights 42.



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CLAIMS

[Claim(s)]

[Claim 1]

While separating a processing object from the undiluted solution which was equipped with the screw conveyor in the ball, came to support these pivotable relatively, and was supplied in said ball In the centrifugal separator which performs washing and deliquoring of said processing object in the screen section prepared along with the inner skin by the side of the end of this ball It is the centrifugal separator which has the penetrant remover receptacle section which accepts in the hub of said screw conveyor the penetrant remover supplied to the interior, and the washing nozzle which spouts the penetrant remover of these penetrant remover receptacle circles toward said screen section,

Two or more penetrant remover discharge holes for residual layers located in a line with said penetrant remover receptacle circles every predetermined spacing along the direction of a whorl of said flight in the location contiguous to the processing object conveyance side of a flight of said screw conveyor and the field of the opposite side are prepared,

A covering flight of the shape of a narrow width prolonged in the direction of a whorl of a flight where a predetermined clearance is left to the field of this opposite side is attached along the periphery edge in the field of the opposite side of said flight,

The centrifugal separator characterized by making the penetrant remover of said penetrant remover receptacle circles which jumps out of said each penetrant remover discharge hole for residual layers blow off from the clearance between said flight periphery edges and said covering flights directly towards the residual layer processing object produced in the clearance between said flight periphery edge and said screen section inner skin.

[Claim 2]

The centrifugal separator according to claim 1 characterized by having formed the diaphragm which divides penetrant remover receptacle circles to the shaft orientations in the screen section of said ball at plurality in said penetrant remover receptacle section, and constituting the washing range in said screen section selectable. [Claim 3]

While separating a processing object from the undiluted solution which was equipped with the screw conveyor in the ball, came to support these pivotable relatively, and was supplied in said ball In the centrifugal separator which performs washing and deliquoring of said processing object in the screen section prepared along with the inner skin by the side of the end of this ball It is the centrifugal separator which has the penetrant remover receptacle section which accepts in the hub of said screw conveyor the penetrant remover supplied to the interior, and the washing nozzle which spouts the penetrant remover of these penetrant remover receptacle circles toward said screen section.

Said penetrant remover receptacle circles divide independently the penetrant remover receptacle section for residual layers which accepts the penetrant remover which washes the residual layer processing object produced in the clearance between the flight periphery edge of said screw conveyor, and said screen section inner skin to said penetrant remover receptacle circles, and prepare it in them,

While preparing two or more communication trunks in the bottom side of said penetrant remover receptacle section for residual layers every predetermined spacing along the direction of a whorl of said flight in the location contiguous to the processing object conveyance side of said flight, and the field of the opposite side, said each communication trunk prepares two or more penetrant remover discharge holes for residual layers which are open for free passage, respectively in the hub of said screw conveyor.

A covering flight of the shape of a narrow width prolonged in the direction of a whorl of a flight where a predetermined clearance is left to the field of this opposite side is attached along the periphery edge in the field of the opposite side of said flight,

The centrifugal separator characterized by turning to said residual layer processing object the penetrant remover of said penetrant remover receptacle circles for residual layers which jumps out of said each penetrant remover discharge hole for residual layers, and making it blow off from the clearance between said flight periphery edges and said covering flights directly.

[Claim 4]

The feed tube for undiluted solution supply prolonged in the shaft orientations is inserted in the interior of the hub of said screw conveyor,

While forming the penetrant remover supply path which supplies a penetrant remover to said penetrant remover

receptacle section in said feed tube, the clear aperture of said penetrant remover supply path is prepared in the middle of the feed tube which laps to said penetrant remover receptacle section radial,

The centrifugal separator according to claim 3 characterized by preparing the clear aperture of said penetrant remover supply path for residual layers in the middle of the feed tube which laps to said penetrant remover receptacle section for residual layers in said feed tube radial while forming the penetrant remover supply path for residual layers which supplies a penetrant remover to said penetrant remover receptacle section for residual layers. [Claim 5]

While separating a processing object from the undiluted solution which was equipped with the screw conveyor in the ball, came to support these pivotable relatively, and was supplied in said ball In the centrifugal separator which performs washing and deliquoring of said processing object in the screen section prepared along with the inner skin by the side of the end of this ball It is the centrifugal separator which has the penetrant remover receptacle section which accepts in the hub of said screw conveyor the penetrant remover supplied to the interior, and the washing nozzle which spouts the penetrant remover of these penetrant remover receptacle circles toward said screen section.

Said penetrant remover receptacle section divides independently the penetrant remover receptacle room for residual layers in which the penetrant remover which washes the residual layer processing object produced in the clearance between the flight periphery edge of this screw conveyor and said screen section inner skin is accepted, and establishes it in the interior of an end the hub of said screw conveyor side.

Where it made said flight penetrate on the periphery of the hub of said screw conveyor, respectively and two or more penetrant remover installation tubing for residual layers is extended to hub shaft orientations at it, a hub circumferencial direction is made to arrange every predetermined spacing, and free passage connection of the end side of each penetrant remover installation tubing for residual layers is made in said penetrant remover receptacle interior of a room for residual layers,

Two or more penetrant remover discharge holes for residual layers located in a line every predetermined spacing along the direction of a whorl of said flight in the location contiguous to the processing object conveyance side of a flight of said screw conveyor and the field of the opposite side in the middle of said each penetrant remover installation tubing for residual layers are prepared.

A covering flight of the shape of a narrow width prolonged in the direction of a whorl of a flight where a predetermined clearance is left to the field of this opposite side is attached along the periphery edge in the field of the opposite side of said flight,

The centrifugal separator characterized by turning to said residual layer processing object the penetrant remover which is introduced in said each penetrant remover installation tubing for residual layers from said penetrant remover receptacle room for residual layers, and jumps out of said each of that penetrant remover discharge hole for residual layers, and making it blow off from the clearance between said flight periphery edges and said covering flights directly.

[Claim 6]

It is the centrifugal separator according to claim 1, 2, 3, 4, or 5 characterized by for said covering flight having given the inclination to which it applies to the side which approaches a flight periphery edge from the side close to said hub to the field of the opposite side in said flight, and a clearance narrows gradually, and attaching it through the support plate located in a line every predetermined spacing.

[Translation done.]

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DETAILED DESCRIPTION

[Detailed Description of the Invention]

[0001]

[Field of the Invention]

While separating a processing object from the undiluted solution which this invention was equipped with the screw conveyor in the ball, came to support these pivotable relatively, and was supplied in said ball In the centrifugal separator which performs washing and deliquoring of said processing object in the screen section prepared along with the inner skin by the side of the end of this ball It is related with the centrifugal separator which has the penetrant remover receptacle section which accepts in the hub of said screw conveyor the penetrant remover supplied to the interior, and the washing nozzle which spouts the penetrant remover of these penetrant remover receptacle circles toward said screen section. Such a centrifugal separator is used for purification of the various crystals in the field of the chemical industry or food stuff industry.

[0002]

[Description of the Prior Art]

If the undiluted solution which consists of a crystalline solid and a crystalline solvent is conventionally supplied in a ball with the centrifugal separator of a screen ball mold, it is divided into the crystal and solvent whose undiluted solution is a processing object within a ball by the centrifugal force, and a crystal will sediment to the inner skin of a ball, will be conveyed by the ball and the screw conveyor to which the very small rotation difference is given, and will receive a deliquoring operation in the taper section in the end side of a ball.

[0003]

In order that the deliquored crystal may make the impurity and the solvent itself which was generally produced in the manufacture process adhere to a crystal front face and may wash these excessive affixes while preparing the screen section in the ball inner circumference side following the taper section, it was washing by preparing the washing nozzle which spouts a penetrant remover toward the part concerned in the hub of a screw conveyor, and injecting a penetrant remover everywhere into the crystal in the middle of conveyance in the screen section (for example, patent reference 1 reference —).

[0004]

[Patent reference 1]

JP,2000-325833,A

[0005]

[Problem(s) to be Solved by the Invention]

However, in the centrifugal separator of a screen ball mold which was mentioned above, in the radial clearance formed between the flight periphery edge of a screw conveyor, and screen section inner skin, when a crystal is not conveyed by conveyor, but the residual layer of a crystal does not have migration and it is pushed against a flight periphery edge by operation of long duration, it will be in the condition of having kept firmly. [0006]

Thus, the crystal which makes a residual layer has the problem of being in the condition of it not only checking the permeability of a penetrant remover, but checking migratory [for being exchanged into a new residual layer crystal]. Generally this condition is called the blinding of a screen. In order to cancel the blinding of a screen, it is necessary to make supply of an undiluted solution suspend and to supply a penetrant remover between fixed time amount instead. Therefore, the stop time of undiluted solution supply can be contributed to production, and had become the factor which reduces productivity.

[0007]

When a penetrant remover was everywhere blown off also about the eye leakage by the screen section further again into the whole crystal currently conveyed with a flight, there was a problem that the crystal of the amount proportional to the volume which passes a crystal layer, and the crystal of the amount proportional to the opening of a screen will produce eye leakage.

[8000]

This invention was made paying attention to the trouble which the above conventional techniques have, and not only making the fall of the productivity accompanying generating of the blinding according to processing objects, such as a crystal, especially in the screen section which is the important section cancel but aims at offering the centrifugal separator which can decrease the eye ullage of the processing object in the screen section in the centrifugal separator of a screen ball mold.

[0009]

[0010]

The place made into the summary of this invention for attaining the purpose mentioned above consists in invention of each following item.

[1] While separating a processing object from the undiluted solution which was equipped with the screw conveyor (40) in the ball (20), came to support these pivotable relatively, and was supplied in said ball (20) In the screen section (30) prepared along with the inner skin by the side of the end of this ball (20) In the centrifugal separator (10 10A) which performs washing and deliquoring of said processing object The penetrant remover receptacle section which accepts in the hub (41) of said screw conveyor (40) the penetrant remover supplied to the interior (43), It is the centrifugal separator (10 10A) which has the washing nozzle (45) which spouts the penetrant remover in this penetrant remover receptacle section (43) toward said screen section (30),

Two or more penetrant remover discharge holes for residual layers (48) located in a line every predetermined spacing along the direction of a whorl of said flight (42) in said penetrant remover receptacle section (43) in the location contiguous to the processing object conveyance side (42a) of a flight (42) of said screw conveyor (40) and the field (42b) of the opposite side are prepared,

A covering flight (50) of the shape of a narrow width prolonged in the direction of a whorl of a flight (42) where a predetermined clearance is left to the field (42b) of this opposite side is attached along the periphery edge in the field (42b) of the opposite side of said flight (42),

The centrifugal separator characterized by making the penetrant remover in said penetrant remover receptacle section (43) which jumps out of said each penetrant remover discharge hole for residual layers (48) blow off from said flight (42) periphery edge and the clearance between said covering flights (50) directly towards the residual layer processing object produced in the clearance between said flight (42) periphery edges and said screen section (30) inner skin (10 10A).

[2] The centrifugal separator given in [1] characterized by having formed the diaphragm (43a) which divides the inside of the penetrant remover receptacle section (43) to the shaft orientations in the screen section (30) of said ball (20) at plurality in said penetrant remover receptacle section (43), and constituting the washing range in said screen section (30) selectable (10A).

[0011]

[3] While separating a processing object from the undiluted solution which was equipped with the screw conveyor (40) in the ball (20), came to support these pivotable relatively, and was supplied in said ball (20) In the screen section (30) prepared along with the inner skin by the side of the end of this ball (20) In the centrifugal separator (10B) which performs washing and deliquoring of said processing object The penetrant remover receptacle section which accepts in the hub (41) of said screw conveyor (40) the penetrant remover supplied to the interior (43), It is the centrifugal separator (10B) which has the washing nozzle (45) which spouts the penetrant remover in this penetrant remover receptacle section (43) toward said screen section (30).

In said penetrant remover receptacle section (43), the inside of said penetrant remover receptacle section (43) is divided independently, and prepares the penetrant remover receptacle section for residual layers (46) which accepts the penetrant remover which washes the residual layer processing object produced in the clearance between the flight (42) periphery edge of said screw conveyor (40), and said screen section (30) inner skin,

In the location contiguous to the processing object conveyance side (42a) of said flight (42), and the field (42b) of the opposite side While preparing two or more communication trunks (47) in the bottom side of said penetrant remover receptacle section for residual layers (46) every predetermined spacing along the direction of a whorl of said flight (42) Said each communication trunk (47) prepares two or more penetrant remover discharge holes for residual layers (48) which are open for free passage, respectively in the hub (41) of said screw conveyor (40), A covering flight (50) of the shape of a narrow width prolonged in the direction of a whorl of a flight (42) where a predetermined clearance is left to the field (42b) of this opposite side is attached along the periphery edge in the field (42b) of the opposite side of said flight (42),

The centrifugal separator characterized by turning to said residual layer processing object the penetrant remover in said penetrant remover receptacle section for residual layers (46) which jumps out of said each penetrant remover discharge hole for residual layers (48), and making it blow off from said flight (42) periphery edge and the clearance between said covering flights (50) directly (10B).

[0012]

[4] Insert in the interior of the hub (41) of said screw conveyor (40) the feed tube for undiluted solution supply (60) prolonged in the shaft orientations,

While forming the penetrant remover supply path (71) which supplies a penetrant remover to said penetrant remover receptacle section (43) in said feed tube (60), the clear aperture of said penetrant remover supply path (71) is prepared in the middle of the feed tube (60) which laps to said penetrant remover receptacle section (43) radial, The centrifugal separator given in [3] characterized by preparing the clear aperture of said penetrant remover supply path for residual layers (72) in the middle of the feed tube (60) which laps to said penetrant remover receptacle section for residual layers (46) in said feed tube (60) radial while forming the penetrant remover supply path for residual layers (72) which supplies a penetrant remover to said penetrant remover receptacle section for residual layers (46) (10B).

[0013]

[5] While separating a processing object from the undiluted solution which was equipped with the screw conveyor

(40) in the ball (20), came to support these pivotable relatively, and was supplied in said ball (20) In the screen section (30) prepared along with the inner skin by the side of the end of this ball (20) In the centrifugal separator (10C) which performs washing and deliquoring of said processing object The penetrant remover receptacle section which accepts in the hub (41) of said screw conveyor (40) the penetrant remover supplied to the interior (43), It is the centrifugal separator (10C) which has the washing nozzle (45) which spouts the penetrant remover in this penetrant remover receptacle section (43) toward said screen section (30),

Said penetrant remover receptacle section (43) divides independently the penetrant remover receptacle room for residual layers (54) in which the penetrant remover which washes the residual layer processing object produced in the clearance between the flight (42) periphery edge of this screw conveyor (40) and said screen section (30) inner skin is accepted, and establishes it in the interior of an end the hub (41) of said screw conveyor (40) side, Where it made said flight (42) penetrate on the periphery of the hub (41) of said screw conveyor (40), respectively and two or more penetrant remover installation tubing for residual layers (53) is extended to hub (41) shaft orientations at it, a hub (41) circumferencial direction is made to arrange every predetermined spacing, and free passage connection of the end side of each penetrant remover installation tubing for residual layers (53) is made into said penetrant remover receptacle room for residual layers (54),

Two or more penetrant remover discharge holes for residual layers (53a) located in a line every predetermined spacing along the direction of a whorl of said flight (42) in the location contiguous to the processing object conveyance side (42a) of a flight (42) of said screw conveyor (40) and the field (42b) of the opposite side in the middle of said each penetrant remover installation tubing for residual layers (53) are prepared,

A covering flight (50) of the shape of a narrow width prolonged in the direction of a whorl of a flight (42) where a predetermined clearance is left to the field (42b) of this opposite side is attached along the periphery edge in the field (42b) of the opposite side of said flight (42),

The centrifugal separator characterized by turning to said residual layer processing object the penetrant remover which is introduced from said penetrant remover receptacle room for residual layers (54) in said each penetrant remover installation tubing for residual layers (53), and jumps out of said each of that penetrant remover discharge hole for residual layers (53a), and making it blow off from said flight (42) periphery edge and the clearance between said covering flights (50) directly (10C).

[0014]

[6] As opposed to the field (42b) of the opposite side [in / in said covering flight (50) / said flight (42)] The inclination to which it applies to the side which approaches a flight (42) periphery edge from the side close to said hub (41), and a clearance narrows gradually is given. The centrifugal separator of [1], [2], [3], [4], or [5] publications which are characterized by attaching through the support plate (51) located in a line every predetermined spacing (10, 10A, 10B, 10C). [0015]

Next, an operation of this invention is explained.

If an undiluted solution is supplied in a ball (20) according to the centrifugal separator (10) given in the above [1], an undiluted solution will be divided into a processing object and a mother liquor by the centrifugal force within a ball (20), a processing object will sediment to the inner skin of a ball (20), and this processing object will be conveyed by the ball (20) and the screw conveyor (40) to which the rotation difference is given. However, in the radial clearance formed between the flight (42) periphery edge of a screw conveyor (40), and screen section (30) inner skin, a processing object is not fully conveyed by conveyor, but makes a residual layer.

[0016]

The processing object which is in the middle of conveyance and was deliquored washes in the screen section (30) prepared along with the inner skin by the side of the end of a ball (20) by blowing off a penetrant remover from the washing nozzle (45) in the hub (41) of a screw conveyor (40) toward a processing object, in order to make the impurity and the mother liquor itself which was produced in the manufacture process adhere to a front face generally and to wash these excessive affixes. A penetrant remover here is supplied to the penetrant remover receptacle section (43) in said hub (41) through the penetrant remover supply path (71) separately established for example, into the feed tube (60) which supplies an undiluted solution in a ball (20).

The penetrant remover in said penetrant remover receptacle section (43) blows off from said washing nozzle (45), and also jumps out of two or more penetrant remover discharge holes for residual layers (48) located in a line every predetermined spacing along the direction of a whorl of a flight (42) in the location contiguous to the processing object conveyance side (42a) of said flight (42), and the field (42b) of the opposite side in a ball (20). Without scattering, along the periphery edge in the field (42b) of the opposite side of a flight (42), a penetrant remover blows off from the thin clearance between a covering flight (50) of the shape of a narrow width prolonged in the direction of a whorl of a flight (42), and a flight (42) periphery edge directly towards a residual layer processing object here, where a predetermined clearance is left to the field (42b) of this opposite side.

[0018]

Thereby, apart from overall washing of the processing object by the washing nozzle (45), since it can carry out by combining local washing especially to a residual layer processing object, fixing of a residual layer processing object is lost, migratory increases and the permeability of the penetrant remover to the whole processing object under conveyance also improves. Therefore, while being able to prevent the blinding of the processing object in the screen section (30), it becomes possible to control the amount of penetrant removers as an object for the permutation of

the impurity in an original processing object, and it becomes possible to also decrease the eye ullage of the processing object in the screen section (30) of it.
[0019]

When the diaphragm (43a) which divides the inside of the penetrant remover receptacle section (43) to the shaft orientations in the screen section (30) of said ball (20) at plurality is formed in said penetrant remover receptacle section (43) like the publication to the above [2], For example, the penetrant remover supply path (71) separately established into the feed tube (60) which supplies an undiluted solution in a ball (20) is minded. It is also possible to supply a penetrant remover in all the partitions of said penetrant remover receptacle section (43), or to limit only in some partitions, and to supply a penetrant remover.

In this case, a penetrant remover blows off only to the screen section (30) of the range which laps the ball (20) radial in the partition of the penetrant remover receptacle section (43) to which the penetrant remover was supplied. Thereby, the washing range in the screen section (30) can be chosen suitably.

[0021]

According to the centrifugal separator (10B) given in the above [3], in said penetrant remover receptacle section (43) The penetrant remover receptacle section for residual layers (46) which accepts the penetrant remover which washes the residual layer of a processing object The penetrant remover which divides independently of the inside of the penetrant remover receptacle section (43), is prepared, and was supplied to this penetrant remover receptacle section for residual layers (46) In the location contiguous to the processing object conveyance side (42a) of said flight (42), and the field (42b) of the opposite side It passes along the communication trunk (47) prepared every predetermined spacing along the direction of a whorl of a flight (42), and jumps out of the penetrant remover discharge hole for residual layers (48) prepared in the hub (41) of said screw conveyor (40). [0022]

The penetrant remover which jumped out in the ball (20) here blows off from the thin clearance between a covering flight (50) of the shape of a narrow width prolonged in the direction of a whorl of a flight (42), and a flight (42) periphery edge directly towards said residual layer processing object along the periphery edge in the field (42b) of the opposite side of said flight (42), without scattering. Thereby, it can raise the permeability of the penetrant remover to a processing object, and migratory [of a residual layer processing object] like the case of the above [1].

[0023]

Moreover, in this centrifugal separator (10B), in order to supply a penetrant remover to the penetrant remover receptacle section (43) and the penetrant remover receptacle section for residual layers (46) in the hub (41) of said screw conveyor (40), as indicated above [4], some feed tubes for undiluted solution supply (60) inserted into a hub (41) can be used effectively.

[0024]

That is, the penetrant remover supply path (71) which supplies a penetrant remover to said penetrant remover receptacle section (43) is formed in a feed tube (60), and the clear aperture of a penetrant remover supply path (71) is prepared in the middle of the feed tube (60) which laps to said penetrant remover receptacle section (43) radial. [0025]

The penetrant remover supply path for residual layers (72) which supplies a penetrant remover to said penetrant remover receptacle section for residual layers (46) is similarly formed in a feed tube (60). If the clear aperture of the penetrant remover supply path for residual layers (72) is prepared in the middle of the feed tube (60) which laps with radial to said penetrant remover receptacle section for residual layers (46) It becomes possible to the penetrant remover receptacle section (43) and the penetrant remover receptacle section for residual layers (46) to supply a penetrant remover efficiently separately.

According to the centrifugal separator (10C) given in the above [5], inside an end said hub (41) side The penetrant remover receptacle room for residual layers (54) in which the penetrant remover which washes the residual layer of a processing object is accepted apart from said penetrant remover receptacle section (43) is prepared. The penetrant remover supplied to this penetrant remover receptacle room for residual layers (54) is introduced into two or more penetrant remover installation tubing for residual layers (53) arranged by the periphery of a hub (41), respectively.

[0027]

[0028]

and the penetrant remover introduced in each penetrant remover installation tubing for residual layers (53) — each penetrant remover installation tubing for residual layers (53) — on the way — two or more penetrant remover discharge holes for residual layers (53a) which are alike and are prepared every predetermined spacing — a passage — the inside of a ball (20) — jumping out . The penetrant remover which jumped out here blows off from the thin clearance between a covering flight (50) of the shape of a narrow width prolonged in the direction of a whorl of a flight (42), and a flight (42) periphery edge directly towards said residual layer processing object along the periphery edge in the field (42b) of the opposite side of said flight (42). Thereby, it can raise the permeability of the penetrant remover to a processing object, and migratory [of a residual layer processing object] like the case of the above [1] and [3].

As opposed to the field (42b) of the opposite side [in / like / further again / the publication to the above [6] / for

said covering flight (50) / said flight (42)] If it attaches through the support plate (51) which gives the inclination to which it applies to the side which approaches a flight (42) periphery edge from the side close to said hub (41), and a clearance narrows gradually, and is located in a line every predetermined spacing The accepted penetrant remover can be made to blow off from the narrow range directly to a residual layer processing object, accepting the penetrant remover which jumps out of said hub (41) side in the large range.

[0029]

[Embodiment of the Invention]

Hereafter, the gestalt of various kinds of operations which represent this invention based on a drawing is explained. Drawing 1 - drawing 3 show the gestalt of the 1st operation of this invention.

The centrifugal separator 10 concerning the gestalt of this operation is called a screen ball mold centrifugal separator, is equipped with a screw conveyor 40 in the approximate circle telescopic ball 20, and it is constituted so that the processing object and mother liquor which are a processing object can be separately separated from the undiluted solution which comes to support these pivotable relatively and is supplied in said ball 20. [0030]

With a processing object, the various crystals in the field of the chemical industry or food stuff industry etc. correspond, and the paraxylene used as the raw material of the terephthalic acid which specifically serves as a PET bottle and a raw material of polyester fiber, and a terephthalic acid, the bisphenol used as the raw material of CD-ROM, the other glutamine soda used as the raw material of chemical condiment, etc. correspond here. Moreover, various kinds of solvents correspond to a mother liquor. Various crystals have adhered the solvent which constitutes the non-polymerization matter and a slurry in the manufacture process to the crystal front face, and the washing permutation of these affixes can be carried out by penetrant removers (another specific solvent etc.). Hereafter, the case where it applies to a crystal as a processing object is explained to an example. [0031]

As shown in <u>drawing 2</u>, the ball 20 and the screw conveyor 40 of the interior are supported to revolve pivotable through Shafts 12a and 12b inside casing 11. The rotation drive of a ball 20 and the screw conveyor 40 is carried out by fine ****** by the differential gear 14 formed successively by the bearing 13 of one side. Explanation well–known [this differential–gear 14 very thing] and detailed is omitted. [0032]

The interior of casing 11 is divided so that it may correspond to the exhaust port 24 prepared in the ball 20 which following-**, the screen section 30, and dam section 26 grade, respectively. And the crystal exhaust port 15 which is open for free passage to said exhaust port 24, the penetrant remover exhaust port 16 which is open for free passage in said screen section 30, and the mother liquor exhaust port 17 which is open for free passage in said dam section 26 are formed in the lower part of casing 11, respectively. [0033]

The end side (it is right-hand side in <u>drawing 2</u>) of a ball 20 serves as an eject direction of a crystal, and it is classified into the parallel cylinder part 21 of a major diameter, the taper section 22 which a bore reduces gradually toward an end side, and the parallel cylinder part 23 of a minor diameter sequentially from the other end side (it is left-hand side in <u>drawing 2</u>) of a ball 20. At the tip side of the parallel cylinder part 23 of a minor diameter, the exhaust port 24 of a crystal is established, and while regulating the radial depth of a ball 20, the mother liquor which separated the crystal is prepared in the dam section 26 which can be discharged out of a ball 20 at the tip side of the parallel cylinder part 21 of a major diameter.

[0034]

As shown in <u>drawing 1</u>, many filtrate discharge holes 25 are formed in the wall surface, an inner circumference side is covered in the direction of the perimeter with the cylinder—like filtering medium 31, and, as for the parallel cylinder part 23 of a minor diameter, the screen section 30 is made. Although the magnitude of the filtrate discharge hole 25 does not need to take the particle diameter of a crystal into consideration so much, a filtering medium 31 consists of the material which has many the micropores thru/or the slits of minor diameter size from the particle diameter of a crystal. It is good to specifically use a wedge wire screen, a porosity ceramic Plastic solid, etc. In addition, as for the inner skin of the parallel cylinder part 23, the front face is deleted by the thickness of a filtering medium 31. [0035]

A screw conveyor 40 consists of a hub 41 used as the revolving shaft, and flight 42 formed in the periphery of this hub 41 in the shape of a screw, and the flight 42 is formed so that a crystal may be conveyed to the end side (it is right-hand side in <u>drawing 2</u>) of a ball 20. In addition, between the periphery edge of flight 42, and the inner skin (filtering-medium 31 front face of the screen section 30) of the parallel cylinder part 23, on the structure rotated at the rate from which a screw conveyor 40 and a ball 20 differ, it is set up so that a clearance may be generated in radial.

[0036]

The penetrant remover receptacle section 43 which accepts the penetrant remover supplied to the interior, and the washing nozzle 45 which spouts the penetrant remover in this penetrant remover receptacle section 43 toward the screen section 30 of said ball 20 are formed in the hub 41. The penetrant remover receptacle section 43 consists of a part surrounded by the partition which extends to predetermined width of face in the direction of an axial center covering the direction of the perimeter of the inner skin of a hub 41. [0037]

The penetrant remover discharge hole 44 is formed in the peripheral wall of the hub 41 which becomes the bottom

side of the penetrant remover receptacle section 43 every predetermined spacing, and the washing nozzle 45 which is open for free passage to the peripheral face side of a hub 41 at said penetrant remover discharge hole 44 protrudes on it. As shown in <u>drawing 1</u>, from the center of a pitch of flight 42, the washing nozzle 45 is an other end side (it is left-hand side in <u>drawing 1</u>) a little, and is allotted to the location which faces the screen section 30 radial here.

[0038]

Furthermore in the penetrant remover receptacle section 43, two or more penetrant remover discharge holes 48 for residual layers located in a line every predetermined spacing along the direction of a whorl of flight 42 in the location which adjoins processing object conveyance side 42a of flight 42 and field 42b of the opposite side are formed. This penetrant remover discharge hole 48 for residual layers is for said washing nozzle 45 to turn independently the penetrant remover in said penetrant remover receptacle section 43 to the residual layer crystal on the screen section 30, and spout it directly.

[0039]

The covering flight 50 of the shape of a narrow width prolonged in the direction of a whorl of flight 42 where a predetermined clearance is left to field 42b of this opposite side is attached along the periphery edge in processing object conveyance side 42a of flight 42, and field 42b of the opposite side. The penetrant remover which jumps out of said penetrant remover discharge hole 48 for residual layers blows off from the clearance between a flight 42 periphery edge and the covering flight 50 directly to said residual layer crystal. [0040]

The covering flight 50 is arranged on the condition that the inclination to which it applies to the side which approaches a flight 42 periphery edge from the side close to said hub 41 to field 42b of the opposite side in flight 42, and a clearance narrows gradually was given, and is attached through the support plate 51 located in a line every predetermined spacing along the direction of a whorl of flight 42.

The feed tube 60 for undiluted solution supply prolonged in the shaft orientations is inserted in the interior of a hub 41. The start edge of a feed tube 60 extends outside, and serves as the undiluted solution feed hopper 61 from a hub 41 or a ball 20, and the termination of a feed tube 60 is allotted in the center of abbreviation of the hub 41 interior, and serves as the undiluted solution outlet 62. Furthermore into the feed tube 60, the penetrant remover supply pipe 71 which supplies a penetrant remover to said penetrant remover receptacle section 43 is inserted. [0042]

The start edge of the penetrant remover supply pipe 71 is making penetrant remover feed hopper 71a which carries out opening to shaft orientations and an abbreviation right angle in the start edge side of a feed tube 60. Moreover, in the middle of the feed tube 60 which laps to the penetrant remover receptacle section 43 radial in a hub 41, clear aperture 71b of the penetrant remover supply pipe 71 is carrying out opening to shaft orientations and an abbreviation right angle.

[0043]

Next, an operation of the centrifugal separator 10 concerning the gestalt of the 1st operation is explained. In <u>drawing 1</u> and <u>drawing 2</u>, an undiluted solution is supplied into a ball 20 through a feed tube 60 using driving sources, such as a pump. The undiluted solution sent from the undiluted solution feed hopper 61 of a feed tube 60 comes out from the undiluted solution outlet 62 located near the abbreviation center in the hub 41 of a screw conveyor 40, and it invests in it by predetermined Mr. Fukashi who set up beforehand in the dam section 26 in a ball 20. As for an undiluted solution, in response to an operation of a centrifugal force, the sedimentation of the crystal is carried out from a mother liquor within a ball 20.

By the flight 42 of a ball 20 and the screw conveyor 40 which rotates by fine ******, the crystal which sedimented to the inner skin side of a ball 20 according to an operation of a centrifugal force is conveyed to the taper section 22 of a ball 20, in case it moves the inner skin top of the taper section 22 to a bore side rather than the depth beforehand set up in the dam section 26, it is deliquored, and it is conveyed further to the screen section 30. [0045]

The crystal which the crystal which is in the middle of conveyance and was deliquored was making the impurity and the mother liquor itself which was produced in the manufacture process adhere to a front face, and resulted in the screen section 30 is washed by the penetrant remover which blows off from the washing nozzle 45 in a hub 41. Generally pure water, an acetic acid, a pure phenol, a sulfuric acid, a hydrochloric acid, etc. are used, and a penetrant remover is supplied to the penetrant remover receptacle section 43 in a hub 41 through the penetrant remover supply pipe 71 separately inserted in the feed tube 60. The penetrant remover accepted in the penetrant remover receptacle section 43 blows off from the washing nozzle 45 through the penetrant remover discharge hole 44 of hub 41 peripheral wall.

[0046]

Thus, although a crystal receives washing and a deliquoring operation in the screen section 30 and it is conveyed further to an exhaust port 24 side, the residual layer of a crystal is formed in the clearance between the flight 42 periphery edge of a screw conveyor 40, and screen section 30 inner skin. This residual layer crystal is washed directly and locally apart from washing by said washing nozzle 45 by the penetrant remover injected from a flight 42 periphery edge.

[0047]

That is, the penetrant remover in the penetrant remover receptacle section 43 jumps out also of two or more penetrant remover discharge holes 48 for residual layers located in a line every predetermined spacing along the direction of a whorl of flight 42 in the location which adjoins processing object conveyance side 42a of flight 42, and field 42b of the opposite side in a ball 20. The penetrant remover which jumped out here blows off from the thin clearance between the covering flight 50 attached along the periphery edge in field 42b of the opposite side of said flight 42, and a flight 42 periphery edge directly towards said residual layer crystal, without scattering. [0048]

As opposed to field 42b of the opposite side [in / as especially the covering flight 50 is shown in drawing 1 / said flight 42] By having given the inclination to which it applies to the side which approaches a flight 42 periphery edge from the side close to a hub 41, and a clearance narrows gradually, and having attached through the support plate 51 located in a line every predetermined spacing The accepted penetrant remover can be made to blow off from the narrow range directly locally to a residual layer crystal, accepting the penetrant remover which jumps out of each penetrant remover discharge hole 48 for residual layers in the large range.

[0049]

As mentioned above, since it can carry out by combining local washing especially to a residual layer processing object apart from washing of the whole crystal by the washing nozzle 45, fixing of a residual layer crystal is lost, migratory increases and the permeability of the penetrant remover to the whole crystal under conveyance also improves. Therefore, while being able to prevent the blinding of the crystal in the screen section 30, it becomes possible to control the amount of penetrant removers as an object for the permutation of the impurity under original crystal, and it becomes possible to decrease the eye ullage of the crystal in the screen section 30 of it. [0050]

In the screen section 30, the penetrant remover which blew off from the washing nozzle 45 and the flight 42 periphery edge is discharged from the filtrate discharge hole 25 through a filtering medium 31 in the exterior of a ball 20 after washing of a crystal or a residual layer crystal. Moreover, the crystal washed and deliquored in the screen section 30 will be discharged by the exterior of a ball 20 from an exhaust port 24, and the last will be collected from the crystal exhaust port 15 in casing 11.

[0051]

Drawing 4 shows the gestalt of the 2nd operation of this invention.

Diaphragm 43a which divides the inside of the penetrant remover receptacle section 43 to the shaft orientations in the screen section 30 of said ball 20 at plurality is prepared in said penetrant remover receptacle section 43, and the washing range in said screen section 30 consists of centrifugal-separator 10A concerning the gestalt of this operation selectable. In addition, the explanation which gave the same sign to the gestalt of the 1st operation and the part of the same kind, and overlapped them is omitted.

[0052]

Into the feed tube 60 inserted in the interior of a hub 41, the penetrant remover supply pipe 71 which was divided by diaphragm 43a in in said penetrant remover receptacle section 43 and which supplies a penetrant remover on the other hand (it is a left-hand side part in <u>drawing 4</u>), and the penetrant remover supply pipe 73 which supplies a penetrant remover to another side (it is a right-hand side part in <u>drawing 4</u>) divided by diaphragm 43a are inserted separately, respectively.

[0053]

The start edge of the penetrant remover supply pipe 71 is making penetrant remover feed hopper 71a which carries out opening to shaft orientations and an abbreviation right angle in the start edge side of a feed tube 60. In the middle of the feed tube 60 which was divided by diaphragm 43a in in the penetrant remover receptacle section 43 in a hub 41 and which receives on the other hand (it is a left-hand side part in drawing 4), and laps with radial, clear aperture 71b of the penetrant remover supply pipe 71 is carrying out opening to shaft orientations and an abbreviation right angle.

[0054]

Moreover, the start edge of the penetrant remover supply pipe 73 is making penetrant remover feed hopper 73a which carries out opening to shaft orientations and an abbreviation right angle in the start edge side of a feed tube 60. In the middle of the feed tube 60 which laps with radial to another side (it is a right-hand side part in <u>drawing 4</u>) divided by diaphragm 43a in in the penetrant remover receptacle section 43 in a hub 41, clear aperture 73b of the penetrant remover supply pipe 73 is carrying out opening to shaft orientations and an abbreviation right angle. [0055]

Although gestalten of this operation are consisted of by one diaphragm 43a so that the inside of the penetrant remover receptacle section 43 may be divided into two at shaft orientations Of course, the inside of the penetrant remover receptacle section 43 may be divided to shaft orientations three, or two diaphragm 43a may be prepared in the others instead of what is limited to this mode, two diaphragm 43a may be prepared, and the inside of the penetrant remover receptacle section 43 may be divided to shaft orientations four.

[0056]

According to the gestalt of such the 2nd operation, it is also possible to supply a penetrant remover in all the partitions of the penetrant remover receptacle section 43, or to limit only in some partitions through the penetrant remover supply path 71 and the penetrant remover supply path 73 which were separately established into the feed tube 60 which supplies an undiluted solution in a ball 20, and to supply a penetrant remover. [0057]

In this case, a penetrant remover blows off only to the screen section 30 of the range which laps ball 20 radial one in the partition of the penetrant remover receptacle section 43 to which the penetrant remover was supplied. Thereby, according to the crystal which is a processing object, the class of penetrant remover, etc., the washing range in the screen section 30 can be chosen suitably. [0058]

Drawing 5 and drawing 6 show the gestalt of the 3rd operation of this invention.

In centrifugal-separator 10B concerning the gestalt of this operation, in said penetrant remover receptacle section 43, the penetrant remover receptacle section 46 for residual layers which accepts the penetrant remover which washes said residual layer crystal divides independently of the inside of the penetrant remover receptacle section 43, and is prepared.

[0059]

[0060]

The penetrant remover receptacle section 46 for residual layers comes to prepare the partition which extends to predetermined width of face in the direction of an axial center in the both ends of a cylinder member covering the direction of the perimeter, a communication trunk 47 protrudes on the bottom side every predetermined spacing, and the penetrant remover receptacle section 46 for residual layers is fixed to the condition of having been isolated from the inner skin of a hub 41 within said penetrant remover receptacle section 43 by each communication trunk 47.

As shown in <u>drawing 5</u>, each communication trunk 47 is allotted every predetermined spacing along the direction of a whorl of flight 42 in the location which adjoins processing object conveyance side 42a of said flight 42, and field 42b of the opposite side, and the penetrant remover discharge hole 48 for residual layers which each communication trunk 47 opens for free passage is formed in the peripheral wall of said hub 41. The penetrant remover of the penetrant remover receptacle section 46 for residual layers which jumps out of the penetrant remover discharge hole 48 for residual layers blows off from the clearance between the covering flight 50 and a flight 42 periphery edge directly to said residual layer crystal.

[0061]

Moreover, into said feed tube 60, the penetrant remover supply pipe 71 which makes the penetrant remover supply path which supplies a penetrant remover to said penetrant remover receptacle section 43, and the penetrant remover supply pipe 72 for residual layers which makes the penetrant remover supply path for residual layers which supplies a penetrant remover to said penetrant remover receptacle section 46 for residual layers are inserted separately, respectively.

[0062]

The start edge of the penetrant remover supply pipe 71 is making penetrant remover feed hopper 71a which carries out opening to shaft orientations and an abbreviation right angle in the start edge side of a feed tube 60. In the middle of the feed tube 60 which laps to the penetrant remover receptacle section 43 radial in a hub 41, clear aperture 71b of the penetrant remover supply pipe 71 is carrying out opening to shaft orientations and an abbreviation right angle.

[0063]

On the other hand, the start edge of the penetrant remover supply pipe 72 for residual layers is making penetrant remover feed hopper 72a for residual layers which carries out opening to shaft orientations and an abbreviation right angle in the start edge side of a feed tube 60. In the middle of the feed tube 60 which laps to the penetrant remover receptacle section 46 for residual layers radial in a hub 41, clear aperture 72b of the penetrant remover supply pipe 72 for residual layers is carrying out opening to shaft orientations and an abbreviation right angle. [0064]

According to the gestalt of the 3rd above operation, the penetrant remover supplied to the penetrant remover receptacle section 46 for residual layers passes along the communication trunk 47 prepared every predetermined spacing along the direction of a whorl of flight 42 in the location which adjoins processing object conveyance side 42a of flight 42, and field 42b of the opposite side, and jumps out of the penetrant remover discharge hole 48 for residual layers prepared in the hub 41 of a screw conveyor 40. [0065]

The penetrant remover which jumped out in the ball 20 can be made to blow off from the thin clearance between the covering flight 50 attached along the periphery edge in field 42b of the opposite side of said flight 42, and a flight 42 periphery edge directly towards said residual layer crystal, without scattering. [0066]

Here in the penetrant remover receptacle section 43 and the penetrant remover receptacle section 46 for residual layers. The volume of the penetrant remover made to blow off from the washing nozzle 45 since a penetrant remover is separately supplied in the condition of having been divided mutually, Since the volume of the penetrant remover made to blow off from the thin clearance between the covering flight 50 and a flight 42 periphery edge is more separately [than the exterior] controllable, the optimal penetrant remover volume for [both] aiming at reduction of the substitutional rate of crystal washing and an eye ullage can be adjusted easily.

[0067]

Drawing 7 and drawing 8 show the gestalt of the 4th operation of this invention.

In centrifugal-separator 10C concerning the gestalt of this operation, the penetrant remover receptacle room 54 for residual layers in which the penetrant remover which washes said residual layer crystal is accepted divides

independently [said penetrant remover receptacle section 43], and is established in the interior of an end the hub 41 of said screw conveyor 40 side. With the gestalt of this operation, the penetrant remover receptacle room 54 for residual layers is established in the latest part of a hub 41. [0068]

In the condition of penetrating said flight 42, respectively and extending in the shaft orientations of a hub 41, two or more penetrant remover installation tubing 53 for residual layers is attached in the periphery of a hub 41 so that it may arrange every predetermined spacing to the circumferencial direction of a hub 41. Penetrant remover free passage hole 54a for residual layers is drilled in the pars basilaris ossis occipitalis of said penetrant remover receptacle room 54 for residual layers, and free passage connection of the end side of each penetrant remover installation tubing 53 for residual layers is made into the penetrant remover receptacle room 54 for residual layers through penetrant remover free passage hole 54a for residual layers, respectively.

Although the other end side of each penetrant remover installation tubing 53 for residual layers is closed, two or more penetrant remover discharge hole 53a for residual layers located in a line every predetermined spacing along the direction of a whorl of flight 42 in the location which adjoins field 42b of the opposite side of said flight 42 in the middle of each penetrant remover installation tubing 53 for residual layers is prepared.

[0070]

The penetrant remover of the penetrant remover receptacle room 54 for residual layers which jumps out of each penetrant remover discharge hole 53for residual layers a blows off from the clearance between said covering flight 50 and a flight 42 periphery edge directly to said residual layer crystal. In addition, in the middle of the feed tube 60 which laps to the penetrant remover receptacle room 54 for residual layers radial in a hub 41, clear aperture 72b of the penetrant remover supply pipe 72 for residual layers is carrying out opening to shaft orientations and an abbreviation right angle.

[0071]

According to the gestalt of the 4th above operation, the penetrant remover supplied to the penetrant remover receptacle room 54 for residual layers is introduced into two or more penetrant remover installation tubing 53 for residual layers arranged by the periphery of a hub 41, respectively, and the penetrant remover introduced in each penetrant remover installation tubing 53 for residual layers — each penetrant remover installation tubing 53 for residual layers — on the way — two or more penetrant remover discharge hole 53a for residual layers which is alike and is prepared every predetermined spacing — a passage — the inside of a ball 20 — jumping out . [0072]

The penetrant remover which jumped out in the ball 20 can be made to blow off from the thin clearance between the covering flight 50 attached along the periphery edge in field 42b of the opposite side of said flight 42, and a flight 42 periphery edge directly towards said residual layer crystal, without scattering. Thereby, a residual layer crystal with each penetrant remover installation tubing 53 for residual layers can be washed separately, and the class and volume of each penetrant remover can also be mutually changed with washing of the processing object by said washing nozzle 45.

[0073]

As mentioned above, although the drawing has explained the gestalt of operation of this invention, according to these concrete configurations, it becomes possible to raise the permeability of the penetrant remover to a crystal, and migratory [of a residual layer crystal]. However, even if this invention has modification and the addition in the range which is not limited to the gestalt of these operations and does not deviate from the summary of this invention, it cannot be overemphasized that it is contained in this invention.

[0074]

[Effect of the Invention]

According to the centrifugal separator concerning this invention, since migratory [of this residual layer] is improved since the residual layer processing object adhering to the inner skin of the screen section can be made to inject a direct penetrant remover, and the permeability of the whole penetrant remover increases, solidification prevention of a residual layer is attained from the flight periphery edge of a screw conveyor by washing only a residual layer processing object locally and making the liquid content of a processing object high. [0075]

Moreover, although the eye leakage of the processing object of the amount proportional to the volume of the penetrant remover which passes processing ****, and the processing object of the amount proportional to the opening of the screen section is produced when a penetrant remover is applied to the whole processing object also about the eye leakage of the screen section Since fixing of a residual layer processing object is lost by injecting a penetrant remover in a residual layer processing object like the above-mentioned more directly than a flight periphery edge and the permeability of the penetrant remover to the processing object under conveyance improves, It becomes possible to control the amount of penetrant removers as an object for the permutation of the impurity in an original processing object, and it becomes possible to decrease the comprehensive eye ullage of the processing object in the screen section of it.

[Brief Description of the Drawings]

[Drawing 1] It is drawing of longitudinal section showing the important section of the centrifugal separator concerning the gestalt of the 1st operation of this invention.

[Drawing 2] It is drawing of longitudinal section showing the whole centrifugal separator concerning the gestalt of

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the 1st operation of this invention.
[Drawing 3] It is the III-III line sectional view of drawing 1.
[Drawing 4] It is drawing of longitudinal section showing the important section of the centrifugal separator
concerning the gestalt of the 2nd operation of this invention.
[Drawing 5] It is drawing of longitudinal section showing the important section of the centrifugal separator
concerning the gestalt of the 3rd operation of this invention.
[Drawing 6] It is the VI-VI line sectional view of drawing 5.
[Drawing 7] It is drawing of longitudinal section showing the important section of the centrifugal separator
concerning the gestalt of the 4th operation of this invention.
[Drawing 8] It is the VIII-VIII line sectional view of drawing 7.
[Description of Notations]
10 — Centrifugal separator
10A — Centrifugal separator
10B — Centrifugal separator
10C - Centrifugal separator
11 — Casing
12a, 12b - Shaft
13 -- Bearing
14 -- Differential gear
15 — Crystal exhaust port
16 - Penetrant remover exhaust port
17 - Mother liquor exhaust port
20 -- Ball
21 -- Parallel cylinder part
22 -- Taper section
23 - Parallel cylinder part
24 — Exhaust port
25 -- Filtrate discharge hole
26 - Dam section
30 — Screen section
31 - Filtering medium
40 - Screw conveyor
41 -- Hub
42 -- Flight
43 - Penetrant remover receptacle section
43a -- Diaphragm
44 -- Penetrant remover discharge hole
45 — Washing nozzle
46 -- The penetrant remover receptacle section for residual layers
47 — Communication trunk
48 — Penetrant remover discharge hole for residual layers
50 - Covering flight
51 - Support plate
53 - Penetrant remover installation tubing for residual layers
54 -- Penetrant remover receptacle room for residual layers
54a -- Penetrant remover free passage hole for residual layers
60 - Feed tube
61 - Undiluted solution feed hopper
62 - Undiluted solution outlet
71 -- Penetrant remover supply pipe
71a -- Penetrant remover feed hopper
71b — Clear aperture
72 - Penetrant remover supply pipe for residual layers
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73 -- Penetrant remover supply pipe

73a -- Penetrant remover feed hopper

73b -- Clear aperture

72b -- Clear aperture

[Translation done.]

72a — Penetrant remover feed hopper for residual layers

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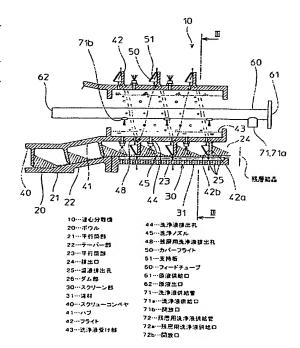
(54) 【発明の名称】 遠心分離機

(57) 【要約】

【課題】スクリーンボウル型の遠心分離機において、その要部であるスクリーン部での特に結晶等の処理物による目詰まりの発生に伴う生産性の低下を解消させるだけでなく、スクリーン部における処理物の目漏れ量を減少させることができる遠心分離機を提供する。

【解決手段】スクリューコンベヤ40のハブ41内部には、洗浄ノズル45用の洗浄液を受け入れる洗浄液受け部43が設けられ、洗浄液受け部43内には、フライト42のらせん方向に沿って所定間隔おきに並ぶ複数の残層用洗浄液排出孔48が設けられている。各残層用洗浄液排出孔48からボウル20内に飛び出す洗浄液は、フライト42の処理物搬送面42aと反対側の面42bに沿ってらせん方向に延びる細幅状のカバーフライト50と、フライト42外周縁との間の細い隙間より、残層処理物に向けて直接噴出される。

【選択図】図1



【特許請求の範囲】

【請求項1】

ボウル内にスクリューコンベヤを備え、これらを相対的に回転可能に支持してなり、前記ボウル内に供給した原液から処理物を分離すると共に、該ボウルの一端側の内周面に沿って設けたスクリーン部で、前記処理物の洗浄および脱液を行う遠心分離機において、前記スクリューコンベヤのハブに、その内部に供給した洗浄液を受け入れる洗浄液受け部と、該洗浄液受け部内の洗浄液を前記スクリーン部に向かって噴出する洗浄ノズルとを有する遠心分離機であって、

前記洗浄液受け部内に、前記スクリューコンベヤのフライトの処理物搬送面と反対側の面に隣接する位置にて、前記フライトのらせん方向に沿って所定間隔おきに並ぶ複数の残層用洗浄液排出孔を設け、

前記フライトの反対側の面における外周縁に沿って、該反対側の面に対して所定の隙間を 空けた状態でフライトのらせん方向に延びる細幅状のカバーフライトを取り付け、

前記各残層用洗浄液排出孔から飛び出す前記洗浄液受け部内の洗浄液を、前記フライト外周縁と前記カバーフライトとの間の隙間より、前記フライト外周縁と前記スクリーン部内周面との間の隙間に生じる残層処理物に向けて直接噴出させることを特徴とする遠心分離機。

【請求項2】

前記洗浄液受け部に、前記ボウルのスクリーン部における軸方向に洗浄液受け部内を複数に区画する仕切り板を設けて、前記スクリーン部における洗浄範囲を選択可能に構成したことを特徴とする請求項1記載の遠心分離機。

【請求項3】

ボウル内にスクリューコンベヤを備え、これらを相対的に回転可能に支持してなり、前記ボウル内に供給した原液から処理物を分離すると共に、該ボウルの一端側の内周面に沿って設けたスクリーン部で、前記処理物の洗浄および脱液を行う遠心分離機において、前記スクリューコンベヤのハブに、その内部に供給した洗浄液を受け入れる洗浄液受け部と、該洗浄液受け部内の洗浄液を前記スクリーン部に向かって噴出する洗浄ノズルとを有する遠心分離機であって、

前記洗浄液受け部内に、前記スクリューコンベヤのフライト外周縁と前記スクリーン部内周面との間の隙間に生じる残層処理物を洗浄する洗浄液を受け入れる残層用洗浄液受け部を、前記洗浄液受け部内とは独立に区画して設け、

前記フライトの処理物搬送面と反対側の面に隣接する位置にて、前記フライトのらせん方向に沿って所定間隔おきに、前記残層用洗浄液受け部の底側に複数の接続管を設けると共に、前記スクリューコンベヤのハブに前記各接続管がそれぞれ連通する複数の残層用洗浄液排出孔を設け、

前記フライトの反対側の面における外周縁に沿って、該反対側の面に対して所定の隙間を 空けた状態でフライトのらせん方向に延びる細幅状のカバーフライトを取り付け、

前記各残層用洗浄液排出孔から飛び出す前記残層用洗浄液受け部内の洗浄液を、前記フライト外周縁と前記カバーフライトとの間の隙間より、前記残層処理物に向けて直接噴出させることを特徴とする遠心分離機。

【請求項4】

前記スクリューコンベヤのハブ内部に、その軸方向に延びる原液供給用のフィードチューブを挿入し、

前記フィードチューブ内に、前記洗浄液受け部に洗浄液を供給する洗浄液供給経路を形成すると共に、前記洗浄液受け部に対して半径方向に重なるフィードチューブの途中に前記洗浄液供給経路の開放口を設け、

前記フィードチューブ内に、前記残層用洗浄液受け部に洗浄液を供給する残層用洗浄液供給経路を形成すると共に、前記残層用洗浄液受け部に対して半径方向に重なるフィードチューブの途中に前記残層用洗浄液供給経路の開放口を設けたことを特徴とする請求項3記載の遠心分離機。

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【請求項5】

ボウル内にスクリューコンベアを備え、これらを相対的に回転可能に支持してなり、前記ボウル内に供給した原液から処理物を分離すると共に、該ボウルの一端側の内周面に沿って設けたスクリーン部で、前記処理物の洗浄および脱液を行う遠心分離機において、前記スクリューコンベアのハブに、その内部に供給した洗浄液を受け入れる洗浄液受け部と、該洗浄液受け部内の洗浄液を前記スクリーン部に向かって噴出する洗浄ノズルとを有する遠心分離機であって、

前記スクリューコンベアのハブの一端側内部に、該スクリューコンベヤのフライト外周縁と前記スクリーン部内周面との間の隙間に生じる残層処理物を洗浄する洗浄液を受け入れる残層用洗浄液受け室を、前記洗浄液受け部とは別に区画して設け、

前記スクリューコンベアのハブの外周に、複数の残層用洗浄液導入管を、それぞれ前記フライトを貫通させてハブ軸方向に延ばした状態で、ハブ円周方向に所定間隔おきに配列させ、各残層用洗浄液導入管の一端側を、前記残層用洗浄液受け室内に連通接続し、

前記各残層用洗浄液導入管の途中に、前記スクリューコンベヤのフライトの処理物搬送面と反対側の面に隣接する位置にて、前記フライトのらせん方向に沿って所定間隔おきに並ぶ複数の残層用洗浄液排出孔を設け、

前記フライトの反対側の面における外周縁に沿って、該反対側の面に対して所定の隙間を 空けた状態でフライトのらせん方向に延びる細幅状のカバーフライトを取り付け、

前記残層用洗浄液受け室から前記各残層用洗浄液導入管内に導入され、その前記各残層用洗浄液排出孔から飛び出す洗浄液を、前記フライト外周縁と前記カバーフライトとの間の隙間より、前記残層処理物に向けて直接噴出させることを特徴とする遠心分離機。

【請求項6】

前記カバーフライトは、前記フライトにおける反対側の面に対して、前記ハブに近接する側からフライト外周縁に近接する側にかけて隙間が次第に狭まる勾配をつけて、所定間隔おきに並ぶ支持板を介して取り付けたことを特徴とする請求項1,2,3,4または5記載の遠心分離機。

【発明の詳細な説明】

[0001]

【発明の属する技術分野】

本発明は、ボウル内にスクリューコンベヤを備え、これらを相対的に回転可能に支持してなり、前記ボウル内に供給した原液から処理物を分離すると共に、該ボウルの一端側の内周面に沿って設けたスクリーン部で、前記処理物の洗浄および脱液を行う遠心分離機において、前記スクリューコンベヤのハブに、その内部に供給した洗浄液を受け入れる洗浄液受け部と、該洗浄液受け部内の洗浄液を前記スクリーン部に向かって噴出する洗浄ノズルとを有する遠心分離機に関する。このような遠心分離機は、化学工業や食品工業の分野における各種結晶の精製に用いられるものである。

[0002]

【従来の技術】

従来、スクリーンボウル型の遠心分離機では、ボウル内に結晶性の固形物と溶媒からなる原液が供給されると、遠心力によりボウル内で原液が処理物である結晶と溶媒とに分けられ、結晶はボウルの内周面に沈降して、ボウルと微少の回転差を与えられているスクリューコンベヤにより搬送され、ボウルの一端側にあるテーパー部にて脱液作用を受ける。

[0003]

脱液された結晶は、一般的にその製造過程で生じた不純物や溶媒そのものを結晶表面に付着させており、これら余分な付着物を洗浄するために、テーパー部に続くボウル内周側にスクリーン部を設けると共に、当該部位に向かって洗浄液を噴出する洗浄ノズルをスクリューコンベヤのハブに設けて、スクリーン部で搬送途中の結晶に洗浄液をくまなく噴射することで洗浄を行っていた(例えば、特許文献 1 参照。)。

[0004]

【特許文献1】

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特開2000-325833号公報

[0005]

【発明が解決しようとする課題】

しかしながら、前述したようなスクリーンボウル型の遠心分離機では、スクリューコンベヤのフライト外周縁とスクリーン部内周面との間に形成される半径方向の隙間において、結晶はコンベヤでは搬送されず、長時間の運転によって結晶の残層は移動がなく、フライト外周縁に押し付けられることにより、固くしまった状態となる。

[0006]

このように残層をなす結晶は、洗浄液の透過性を阻害するばかりでなく、新しい残層結晶に入れ替わるための移動性も阻害する状態となってしまうという問題がある。かかる状態は、一般的にスクリーンの目詰まりと呼ばれている。スクリーンの目詰まりを解消するためには、原液の供給を一時停止させ、代わりに一定時間の間、洗浄液を供給する必要がある。そのため、原液供給の停止時間は生産に寄与できないことになり、生産性を低下させる要因となっていた。

[0007]

さらにまた、スクリーン部での目漏れについても、フライトで搬送されている結晶全体にくまなく洗浄液を噴出した場合には、結晶層を通過する液量に比例した量の結晶と、スクリーンの目開きに比例した量の結晶が目漏れを生じてしまうという問題があった。

[0008]

本発明は、以上のような従来技術が有する問題点に着目してなされたもので、スクリーンボウル型の遠心分離機において、その要部であるスクリーン部での特に結晶等の処理物による目詰まりの発生に伴う生産性の低下を解消させるだけでなく、スクリーン部における処理物の目漏れ量を減少させることができる遠心分離機を提供することを目的としている

[00009]

前述した目的を達成するための本発明の要旨とするところは、次の各項の発明に存する。 [1] ボウル(20)内にスクリューコンベヤ(40)を備え、これらを相対的に回転可能に支持してなり、前記ボウル(20)内に供給した原液から処理物を分離すると共に、該ボウル(20)の一端側の内周面に沿って設けたスクリーン部(30)で、前記処理物の洗浄および脱液を行う遠心分離機(10,10A)において、前記スクリューコンベヤ(40)のハブ(41)に、その内部に供給した洗浄液を受け入れる洗浄液受け部(43)と、該洗浄液受け部(43)内の洗浄液を前記スクリーン部(30)に向かって噴出する洗浄ノズル(45)とを有する遠心分離機(10,10A)であって、前記洗浄液受け部(43)内に、前記スクリューコンベヤ(40)のフライト(42)の

処理物搬送面(42a)と反対側の面(42b)に隣接する位置にて、前記フライト(4 2)のらせん方向に沿って所定間隔おきに並ぶ複数の残層用洗浄液排出孔(48)を設け

前記フライト(42)の反対側の面(42b)における外周縁に沿って、該反対側の面(42b)に対して所定の隙間を空けた状態でフライト(42)のらせん方向に延びる細幅状のカバーフライト(50)を取り付け、

前記各残層用洗浄液排出孔(48)から飛び出す前記洗浄液受け部(43)内の洗浄液を、前記フライト(42)外周縁と前記カバーフライト(50)との間の隙間より、前記フライト(42)外周縁と前記スクリーン部(30)内周面との間の隙間に生じる残層処理物に向けて直接噴出させることを特徴とする遠心分離機(10,10A)。

[0010]

[2] 前記洗浄液受け部(43)に、前記ボウル(20)のスクリーン部(30)における軸方向に洗浄液受け部(43)内を複数に区画する仕切り板(43a)を設けて、前記スクリーン部(30)における洗浄範囲を選択可能に構成したことを特徴とする[1]記載の遠心分離機(10A)。

[0011]

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[3]ボウル(20)内にスクリューコンベヤ(40)を備え、これらを相対的に回転可能に支持してなり、前記ボウル(20)内に供給した原液から処理物を分離すると共に、該ボウル(20)の一端側の内周面に沿って設けたスクリーン部(30)で、前記処理物の洗浄および脱液を行う遠心分離機(10B)において、前記スクリューコンベヤ(40)のハブ(41)に、その内部に供給した洗浄液を受け入れる洗浄液受け部(43)と、該洗浄液受け部(43)内の洗浄液を前記スクリーン部(30)に向かって噴出する洗浄ノズル(45)とを有する遠心分離機(10B)であって、

前記洗浄液受け部(43)内に、前記スクリューコンベヤ(40)のフライト(42)外周緑と前記スクリーン部(30)内周面との間の隙間に生じる残層処理物を洗浄する洗浄液を受け入れる残層用洗浄液受け部(46)を、前記洗浄液受け部(43)内とは独立に区画して設け、

前記フライト(42)の処理物搬送面(42a)と反対側の面(42b)に隣接する位置にて、前記フライト(42)のらせん方向に沿って所定間隔おきに、前記残層用洗浄液受け部(46)の底側に複数の接続管(47)を設けると共に、前記スクリューコンベヤ(40)のハブ(41)に前記各接続管(47)がそれぞれ連通する複数の残層用洗浄液排出孔(48)を設け、

前記フライト(42)の反対側の面(42b)における外周縁に沿って、該反対側の面(42b)に対して所定の隙間を空けた状態でフライト(42)のらせん方向に延びる細幅状のカバーフライト(50)を取り付け、

前記各残層用洗浄液排出孔(48)から飛び出す前記残層用洗浄液受け部(46)内の洗浄液を、前記フライト(42)外周縁と前記カバーフライト(50)との間の隙間より、前記残層処理物に向けて直接噴出させることを特徴とする遠心分離機(10B)。

[0012]

[4]前記スクリューコンベヤ(40)のハブ(41)内部に、その軸方向に延びる原液供給用のフィードチューブ(60)を挿入し、

前記フィードチューブ(60)内に、前記洗浄液受け部(43)に洗浄液を供給する洗浄液供給経路(71)を形成すると共に、前記洗浄液受け部(43)に対して半径方向に重なるフィードチューブ(60)の途中に前記洗浄液供給経路(71)の開放口を設け、前記フィードチューブ(60)内に、前記残層用洗浄液受け部(46)に洗浄液を供給する残層用洗浄液供給経路(72)を形成すると共に、前記残層用洗浄液受け部(46)に対して半径方向に重なるフィードチューブ(60)の途中に前記残層用洗浄液供給経路(72)の開放口を設けたことを特徴とする[3]記載の遠心分離機(10B)。

[0013]

[5] ボウル(20)内にスクリューコンベヤ(40)を備え、これらを相対的に回転可能に支持してなり、前記ボウル(20)内に供給した原液から処理物を分離すると共に、該ボウル(20)の一端側の内周面に沿って設けたスクリーン部(30)で、前記処理物の洗浄および脱液を行う遠心分離機(10C)において、前記スクリューコンベヤ(40)のハブ(41)に、その内部に供給した洗浄液を受け入れる洗浄液受け部(43)と、該洗浄液受け部(43)内の洗浄液を前記スクリーン部(30)に向かって噴出する洗浄ノズル(45)とを有する遠心分離機(10C)であって、

前記スクリューコンベヤ(40)のハブ(41)の一端側内部に、該スクリューコンベヤ(40)のフライト(42)外周縁と前記スクリーン部(30)内周面との間の隙間に生じる残屠処理物を洗浄する洗浄液を受け入れる残屠用洗浄液受け室(54)を、前記洗浄液受け部(43)とは別に区画して設け、

前記スクリューコンベヤ(40)のハブ(41)の外周に、複数の残層用洗浄液導入管(53)を、それぞれ前記フライト(42)を貫通させてハブ(41)軸方向に延ばした状態で、ハブ(41)円周方向に所定間隔おきに配列させ、各残層用洗浄液導入管(53)の一端側を、前記残層用洗浄液受け室(54)内に連通接続し、

前記各残層用洗浄液導入管(53)の途中に、前記スクリューコンベヤ(40)のフライト(42)の処理物搬送面(42a)と反対側の面(42b)に隣接する位置にて、前記

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フライト (42) のらせん方向に沿って所定間隔おきに並ぶ複数の残層用洗浄液排出孔 (53a) を設け、

前記フライト(42)の反対側の面(42b)における外周縁に沿って、該反対側の面(42b)に対して所定の隙間を空けた状態でフライト(42)のらせん方向に延びる細幅状のカバーフライト(50)を取り付け、

前記残層用洗浄液受け室(54)から前記各残層用洗浄液導入管(53)内に導入され、その前記各残層用洗浄液排出孔(53a)から飛び出す洗浄液を、前記フライト(42)外周縁と前記カバーフライト(50)との間の隙間より、前記残層処理物に向けて直接噴出させることを特徴とする遠心分離機(10C)。

[0014]

[6] 前記カバーフライト(50)は、前記フライト(42)における反対側の面(42b)に対して、前記ハブ(41)に近接する側からフライト(42)外周縁に近接する側にかけて隙間が次第に狭まる勾配をつけて、所定間隔おきに並ぶ支持板(51)を介して取り付けたことを特徴とする[1], [2], [3], [4]または[5]記載の遠心分離機(10,10A,10B,10C)。

[0015]

次に本発明の作用を説明する。

前記 [1] に記載の遠心分離機(10)によれば、ボウル(20)内に原液が供給されると、遠心力によりボウル(20)内で原液が処理物と母液とに分けられ、処理物はボウル(20)の内周面に沈降し、かかる処理物は、ボウル(20)と回転差を与えられているスクリューコンベヤ(40)により搬送される。ただし、スクリューコンベヤ(40)のフライト(42)外周縁とスクリーン部(30)内周面との間に形成される半径方向の隙間では、処理物はコンベヤで十分には搬送されず残層をなす。

[0016]

搬送途中で脱液された処理物は、一般にその製造過程で生じた不純物や母液そのものを表面に付着させており、これら余分な付着物を洗浄するために、ボウル(20)の一端側の内周面に沿って設けたスクリーン部(30)において、スクリューコンベヤ(40)のハブ(41)にある洗浄ノズル(45)より処理物に向かって洗浄液を噴出して洗浄を行う。ここでの洗浄液は、例えば、ボウル(20)内に原液を供給するフィードチューブ(60)中に別途設けた洗浄液供給経路(71)を介して、前記ハブ(41)内にある洗浄液受け部(43)に供給される。

[0017]

前記洗浄液受け部(43)内の洗浄液は、前記洗浄ノズル(45)より噴出されるほか、前記フライト(42)の処理物搬送面(42a)と反対側の面(42b)に隣接する位置にて、フライト(42)のらせん方向に沿って所定間隔おきに並ぶ複数の残層用洗浄液排出孔(48)からボウル(20)内に飛び出す。ここで洗浄液は飛び散ることなく、フライト(42)の反対側の面(42b)における外周縁に沿って、該反対側の面(42b)に対して所定の隙間を空けた状態でフライト(42)のらせん方向に延びる細幅状のカバーフライト(50)と、フライト(42)外周縁との間の細い隙間より、残層処理物に向けて直接噴出される。

[0018]

それにより、洗浄ノズル(45)による処理物の全体的な洗浄とは別に、特に残層処理物に対する局所的な洗浄も併せて行うことができるので、残層処理物の固着がなくなり移動性も高まり、搬送中の処理物全体に対する洗浄液の透過性も向上する。従って、スクリーン部(30)における処理物の目詰まりを未然に防ぐことができると共に、本来の処理物中の不純物の置換用としての洗浄液量を抑制することが可能になり、スクリーン部(30)における処理物の目漏れ量も減少させることが可能となる。

$[0\ 0\ 1\ 9\]$

前記[2]に記載のように、前記洗浄液受け部(43)に、前記ボウル(20)のスクリーン部(30)における軸方向に洗浄液受け部(43)内を複数に区画する仕切り板(4

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3 a) を設けた場合、例えば、ボウル(2 0) 内に原液を供給するフィードチューブ(6 0) 中に別途設けた洗浄液供給経路(7 1)を介して、前記洗浄液受け部(4 3)の総ての区画内に洗浄液を供給しても良く、あるいは一部の区画内のみに限定して洗浄液を供給することも可能である。

[0020]

かかる場合に、洗浄液が供給された洗浄液受け部(43)の区画内に、ボウル(20)半径方向に重なる範囲のスクリーン部(30)に対してのみ洗浄液が噴出される。それにより、スクリーン部(30)における洗浄範囲を適宜選択することができる。

[0021]

前記 [3] に記載の遠心分離機(10B)によれば、前記洗浄液受け部(43)内には、処理物の残層を洗浄する洗浄液を受け入れる残層用洗浄液受け部(46)が、洗浄液受け部(43)内とは独立に区画して設けられており、この残層用洗浄液受け部(46)に供給された洗浄液は、前記フライト(42)の処理物搬送面(42a)と反対側の面(42b)に隣接する位置にて、フライト(42)のらせん方向に沿って所定間隔おきに設けられている接続管(47)を通り、前記スクリューコンベヤ(40)のハブ(41)に設けられている残層用洗浄液排出孔(48)から飛び出す。

[0022]

ここでボウル(20)内に飛び出した洗浄液は飛び散ることなく、前記フライト(42)の反対側の面(42b)における外周縁に沿って、フライト(42)のらせん方向に延びる細幅状のカバーフライト(50)と、フライト(42)外周縁との間の細い隙間より、前記残層処理物に向けて直接噴出される。それにより、前記[1]の場合と同様に、処理物に対する洗浄液の透過性および残層処理物の移動性を高めることができる。

[0023]

また、本遠心分離機(10B)において、前記スクリューコンベヤ(40)のハブ(41)内にある洗浄液受け部(43)と残層用洗浄液受け部(46)とに洗浄液を供給するには、前記[4]に記載したように、ハブ(41)内に挿入する原液供給用のフィードチューブ(60)の一部を有効に利用することができる。

[0024]

すなわち、フィードチューブ(60)内に、前記洗浄液受け部(43)に洗浄液を供給する洗浄液供給経路(71)を形成し、前記洗浄液受け部(43)に対して半径方向に重なるフィードチューブ(60)の途中に洗浄液供給経路(71)の開放口を設ける。

[0025]

同様にフィードチューブ(60)内に、前記残層用洗浄液受け部(46)に洗浄液を供給する残層用洗浄液供給経路(72)を形成し、前記残層用洗浄液受け部(46)に対して半径方向に重なるフィードチューブ(60)の途中に残層用洗浄液供給経路(72)の開放口を設ければ、洗浄液受け部(43)および残層用洗浄液受け部(46)に対して、別々に洗浄液を効率よく供給することが可能となる。

[0026]

前記 [5] に記載の遠心分離機(10C)によれば、前記ハブ(41)の一端側内部に、前記洗浄液受け部(43)とは別に、処理物の残層を洗浄する洗浄液を受け入れる残層用洗浄液受け室(54)が設けられており、この残層用洗浄液受け室(54)に供給された洗浄液は、ハブ(41)の外周に配列されている複数の残層用洗浄液導入管(53)にそれぞれ導入される。

[0027]

そして、各残層用洗浄液導入管(53)内に導入された洗浄液は、各残層用洗浄液導入管(53)の途中に所定間隔おきに設けられている複数の残層用洗浄液排出孔(53a)を通り、ボウル(20)内に飛び出す。ここで飛び出した洗浄液は、前記フライト(42)の反対側の面(42b)における外周縁に沿って、フライト(42)のらせん方向に延びる細幅状のカバーフライト(50)と、フライト(42)外周縁との間の細い隙間より、前記残層処理物に向けて直接噴出される。それにより、前記[1],[3]の場合と同様

に、処理物に対する洗浄液の透過性および残層処理物の移動性を高めることができる。

[0028]

さらにまた、前記 [6] に記載のように、前記カバーフライト(50) を、前記フライト(42)における反対側の面(42b)に対して、前記ハブ(41)に近接する側からフライト(42)外周縁に近接する側にかけて隙間が次第に狭まる勾配をつけて、所定間隔おきに並ぶ支持板(51)を介して取り付ければ、前記ハブ(41)側から飛び出す洗浄液を広い範囲で受け入れつつ、受け入れた洗浄液を狭い範囲より残層処理物に対して直接噴出させることができる。

[0029]

【発明の実施の形態】

以下、図面に基づき本発明を代表する各種の実施の形態を説明する。

図1~図3は本発明の第1実施の形態を示している。

本実施の形態に係る遠心分離機10は、スクリーンボウル型遠心分離機と称されるものであり、略円筒型のボウル20内にスクリューコンベヤ40を備え、これらを相対的に回転可能に支持してなり、前記ボウル20内に供給される原液から処理対象である処理物と母液を別々に分離することができるように構成されている。

[0030]

ここで処理物とは、化学工業や食品工業の分野における各種結晶等が該当し、具体的には例えば、ペットボトルやポリエステル繊維の原料となるテレフタル酸、テレフタル酸の原料となるパラキシレン、CD-ROMの原料となるビスフェノール、その他、化学調味料の原料となるグルタミンソーダ等が該当する。また母液には各種の溶媒が該当する。各種結晶は、その製造過程において未重合物質やスラリーを構成する溶媒を結晶表面に付着しており、これらの付着物は洗浄液(特定の別な溶媒等)により洗浄置換することができる。以下、処理物として結晶に適用した場合を例に説明する。

[0031]

図2に示すように、ボウル20とその内部のスクリューコンベヤ40は、ケーシング11の内部にシャフト12a, 12bを介して回転可能に軸支されている。ボウル20およびスクリューコンベヤ40は、片側の軸受け13に連設された差動装置14によって微少差速で回転駆動される。かかる差動装置14自体は公知であり詳細な説明は省略する。

[0032]

ケーシング 1 1 の内部は、次述するボウル 2 0 に設けられている排出口 2 4 、スクリーン部 3 0、ダム部 2 6 等にそれぞれ対応するように区画されている。そして、ケーシング 1 1 の下部には、前記排出口 2 4 に連通する結晶排出口 1 5、前記スクリーン部 3 0 に連通する洗浄液排出口 1 6、前記ダム部 2 6 に連通する母液排出口 1 7 がそれぞれ設けられている。

[0033]

ボウル20の一端側(図2中で右側)が結晶の排出方向となっており、ボウル20の他端側(図2中で左側)から順に、大径の平行筒部21と、一端側に向かって内径が漸次縮小するテーパー部22と、小径の平行筒部23とに区分けされている。小径の平行筒部23の先端側には、結晶の排出口24が開設され、大径の平行筒部21の先端側には、ボウル20の半径方向の液深を規制すると共に、結晶を分離した母液をボウル20外へ排出可能なダム部26が設けられている。

[0034]

図1に示すように、小径の平行筒部23は、その壁面に多数の濾液排出孔25が形成され、内周側が円筒状の濾材31で全周方向に覆われて、スクリーン部30をなしている。濾液排出孔25の大きさは、結晶の粒子径をさほど考慮する必要はないが、濾材31は、結晶の粒子径より小径サイズの多数の微小孔ないしスリットを有する素材から成る。具体的には例えば、ウェッジワイヤースクリーンや多孔質セラミック成形体等を用いるとよい。なお、平行筒部23の内周面は濾材31の厚さ分だけ表面が削られている。

[0035]

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スクリューコンベヤ40は、その回転軸となるハブ41と、該ハブ41の外周にスクリュー状に設けられるフライト42とからなり、フライト42は、結晶をボウル20の一端側(図2中で右側)へ搬送するように形成されている。なお、フライト42の外周縁と平行筒部23の内周面(スクリーン部30の濾材31表面)との間には、スクリューコンベヤ40とボウル20とが異なる速度で回転する構造上、半径方向に隙間が生じるように設定されている。

[0036]

ハブ 4 1 には、その内部に供給された洗浄液を受け入れる洗浄液受け部 4 3 と、該洗浄液受け部 4 3 内の洗浄液を前記ボウル 2 0 のスクリーン部 3 0 に向かって噴出する洗浄ノズル 4 5 とが設けられている。洗浄液受け部 4 3 は、ハブ 4 1 の内周面の全周方向に亘り軸心方向に所定幅に延出する仕切りで囲まれた部位からなる。

[0037]

洗浄液受け部43の底側となるハブ41の周壁には、所定間隔おきに洗浄液排出孔44が設けられ、ハブ41の外周面側に、前記洗浄液排出孔44に連通する洗浄ノズル45が突設されている。ここで洗浄ノズル45は、図1に示すようにフライト42のピッチ中央よりやや他端側(図1中で左側)で、スクリーン部30を半径方向に臨む位置に配されている。

[0038]

さらに洗浄液受け部43内には、フライト42の処理物搬送面42aと反対側の面42bに隣接する位置にて、フライト42のらせん方向に沿って所定間隔おきに並ぶ複数の残層用洗浄液排出孔48は、前記洗浄液受け部43内の洗浄液を、前記洗浄ノズル45とは別に、スクリーン部30上の残層結晶に向けて直接噴出するためのものである。

[0039]

フライト42の処理物搬送面42aと反対側の面42bにおける外周縁に沿って、該反対側の面42bに対して所定の隙間を空けた状態でフライト42のらせん方向に延びる細幅状のカバーフライト50が取り付けられている。前記残層用洗浄液排出孔48から飛び出す洗浄液は、フライト42外周縁とカバーフライト50との間の隙間より、前記残層結晶に対して直接噴出されるようになっている。

[0040]

カバーフライト50は、フライト42における反対側の面42bに対して、前記ハブ41に近接する側からフライト42外周縁に近接する側にかけて隙間が次第に狭まる勾配がつけられた状態に配され、フライト42のらせん方向に沿って所定間隔おきに並ぶ支持板51を介して取り付けられている。

[0041]

ハブ41の内部には、その軸方向に延びる原液供給用のフィードチューブ60が挿入されている。フィードチューブ60の始端は、ハブ41やボウル20より外部に延出し原液供給口61となり、フィードチューブ60の終端は、ハブ41内部の略中央に配されて原液出口62となる。さらにフィードチューブ60内には、前記洗浄液受け部43に洗浄液を供給する洗浄液供給管71が挿入されている。

[0042]

洗浄液供給管71の始端は、フィードチューブ60の始端側にて軸方向と略直角に開口する洗浄液供給口71aをなしている。また、ハブ41内において洗浄液受け部43に対して半径方向に重なるフィードチューブ60の途中には、洗浄液供給管71の開放口71bが軸方向と略直角に開口している。

[0043]

次に、第1実施の形態に係る遠心分離機10の作用を説明する。

図1,図2において、原液はフィードチューブ60を介して、ポンプ等の駆動源を用いてボウル20内へ供給される。フィードチューブ60の原液供給口61から送られた原液は、スクリューコンベヤ40のハブ41内の略中央付近に位置する原液出口62から出て、

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ボウル20内のダム部26で予め設定した所定の深さまで張り込まれる。原液はボウル20内で遠心力の作用を受けて、母液から結晶が沈降分離される。

[0044]

遠心力の作用によりボウル20の内周面側へ沈降した結晶は、ボウル20と微少差速で回転するスクリューコンベヤ40のフライト42によって、ボウル20のテーパー部22へ搬送され、予めダム部26で設定されている液深よりも内径側へテーパー部22の内周面上を移動する際に脱液されて、さらにスクリーン部30へ搬送される。

[0045]

搬送途中で脱液された結晶は、その製造過程で生じた不純物や母液そのものを表面に付着させており、スクリーン部30に至った結晶は、ハブ41にある洗浄ノズル45から噴出される洗浄液によって洗浄される。洗浄液は、一般に純水、酢酸、純フェノール、硫酸、塩酸等が用いられ、フィードチューブ60に別途挿入してある洗浄液供給管71を介して、ハブ41内にある洗浄液受け部43に供給される。洗浄液受け部43に受け入れられた洗浄液は、ハブ41周壁の洗浄液排出孔44を通り洗浄ノズル45から噴出される。

[0046]

このようにスクリーン部 3 0 で結晶は洗浄および脱液作用を受け、さらに排出口 2 4 側へ搬送されるが、スクリューコンベヤ 4 0 のフライト 4 2 外周縁とスクリーン部 3 0 内周面との間の隙間には結晶の残層が形成される。かかる残層結晶は、前記洗浄ノズル 4 5 による洗浄とは別に、フライト 4 2 外周縁から噴射される洗浄液により直接的かつ局所的に洗浄される。

[0047]

すなわち、洗浄液受け部43内の洗浄液は、フライト42の処理物搬送面42aと反対側の面42bに隣接する位置にて、フライト42のらせん方向に沿って所定間隔おきに並ぶ複数の残層用洗浄液排出孔48からもボウル20内に飛び出す。ここで飛び出した洗浄液は飛び散ることなく、前記フライト42の反対側の面42bにおける外周縁に沿って取り付けられたカバーフライト50と、フライト42外周縁との間の細い隙間より、前記残層結晶に向けて直接噴出される。

[0048]

特にカバーフライト 5 0 は、図 1 に示すように、前記フライト 4 2 における反対側の面 4 2 b に対して、ハブ 4 1 に近接する側からフライト 4 2 外周縁に近接する側にかけて隙間が次第に狭まる勾配をつけて、所定間隔おきに並ぶ支持板 5 1 を介して取り付けたことにより、各残層用洗浄液排出孔 4 8 から飛び出す洗浄液を広い範囲で受け入れつつ、受け入れた洗浄液を狭い範囲より残層結晶に対して局所的に直接噴出させることができる。

[0049]

以上のように、洗浄ノズル45による結晶全体の洗浄とは別に、特に残層処理物に対する局所的な洗浄も併せて行うことができるので、残層結晶の固着がなくなり移動性も高まり、搬送中の結晶全体に対する洗浄液の透過性も向上する。そのため、スクリーン部30における結晶の目詰まりを未然に防ぐことができると共に、本来の結晶中の不純物の置換用としての洗浄液量を抑制することが可能になり、スクリーン部30における結晶の目漏れ量を減少させることが可能となる。

[0050]

スクリーン部30において、洗浄ノズル45およびフライト42外周縁より噴出された洗浄液は、結晶や残層結晶の洗浄後に濾材31を通り濾液排出孔25からボウル20の外部へ排出される。また、スクリーン部30で洗浄され脱液された結晶は、排出口24からボウル20の外部に排出され、最後はケーシング11にある結晶排出口15から回収されることになる。

[0051]

図4は本発明の第2実施の形態を示している。

本実施の形態に係る遠心分離機 1 0 Aでは、前記洗浄液受け部 4 3 に、前記ボウル 2 0 のスクリーン部 3 0 における軸方向に洗浄液受け部 4 3 内を複数に区画する仕切り板 4 3 a

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を設けて、前記スクリーン部 3 0 における洗浄範囲を選択可能に構成している。なお、第 1 実施の形態と同種の部位には同一符号を付して重複した説明を省略する。

[0052]

ハブ41の内部に挿入されているフィードチューブ60内には、前記洗浄液受け部43内のうち仕切り板43aで区画された一方(図4中で左側部分)に洗浄液を供給する洗浄液供給管71と、仕切り板43aで区画された他方(図4中で右側部分)に洗浄液を供給する洗浄液供給管73とが、それぞれ別々に挿入されている。

[0053]

洗浄液供給管71の始端は、フィードチューブ60の始端側にて軸方向と略直角に開口する洗浄液供給口71aをなしている。ハブ41内の洗浄液受け部43内のうち仕切り板43aで区画された一方(図4中で左側部分)に対して半径方向に重なるフィードチューブ60の途中には、洗浄液供給管71の開放口71bが軸方向と略直角に開口している。

[0054]

また、洗浄液供給管73の始端は、フィードチューブ60の始端側にて軸方向と略直角に開口する洗浄液供給口73aをなしている。ハブ41内の洗浄液受け部43内のうち仕切り板43aで区画された他方(図4中で右側部分)に対して半径方向に重なるフィードチューブ60の途中には、洗浄液供給管73の開放口73bが軸方向と略直角に開口している。

[0055]

本実施の形態では、1つの仕切り板43aにより、洗浄液受け部43内を軸方向に2分割するように構成されているが、もちろん、この態様に限定されるものではなく、他に例えば、2つの仕切り板43aを設けて洗浄液受け部43内を軸方向に3つに区画したり、あるいは、2つの仕切り板43aを設けて洗浄液受け部43内を軸方向に4つに区画してもよい。

[0056]

このような第2実施の形態によれば、ボウル20内に原液を供給するフィードチューブ6 0中に別途設けた洗浄液供給経路71や洗浄液供給経路73を介して、洗浄液受け部43 の総ての区画内に洗浄液を供給しても良く、あるいは一部の区画内のみに限定して洗浄液 を供給することも可能である。

[0057]

かかる場合に、洗浄液が供給された洗浄液受け部43の区画内に、ボウル20半径方向に重なる範囲のスクリーン部30に対してのみ洗浄液が噴出される。それにより、処理物である結晶や洗浄液の種類等に応じて、スクリーン部30における洗浄範囲を適宜選択することができる。

[0058]

図5および図6は本発明の第3実施の形態を示している。

本実施の形態に係る遠心分離機10Bでは、前記洗浄液受け部43内に、前記残層結晶を洗浄する洗浄液を受け入れる残層用洗浄液受け部46が、洗浄液受け部43内とは独立に 区画して設けられている。

[0059]

残層用洗浄液受け部46は、円筒部材の両端に全周方向に亘り軸心方向に所定幅に延出する仕切りを設けてなり、その底側には、所定間隔おきに接続管47が突設され、各接続管47によって残層用洗浄液受け部46は、前記洗浄液受け部43内にてハブ41の内周面より離隔した状態に固設されている。

[0060]

図 5 に示すように各接続管 4 7 は、前記フライト 4 2 の処理物搬送面 4 2 a と反対側の面 4 2 b に隣接する位置にて、フライト 4 2 のらせん方向に沿って所定間隔おきに配されており、前記ハブ 4 1 の周壁には、各接続管 4 7 が連通する残層用洗浄液排出孔 4 8 が設けられている。残層用洗浄液排出孔 4 8 から飛び出す残層用洗浄液受け部 4 6 の洗浄液は、カバーフライト 5 0 とフライト 4 2 外周縁との間の隙間より、前記残層結晶に対して直接

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噴出されるようになっている。

[0061]

また、前記フィードチューブ60内には、前記洗浄液受け部43に洗浄液を供給する洗浄液供給経路をなす洗浄液供給管71と、前記残層用洗浄液受け部46に洗浄液を供給する残層用洗浄液供給経路をなす残層用洗浄液供給管72とが、それぞれ別々に挿入されている。

[0062]

洗浄液供給管71の始端は、フィードチューブ60の始端側にて軸方向と略直角に開口する洗浄液供給口71aをなしている。ハブ41内において洗浄液受け部43に対して半径方向に重なるフィードチューブ60の途中には、洗浄液供給管71の開放口71bが軸方向と略直角に開口している。

[0063]

一方、残層用洗浄液供給管72の始端は、フィードチューブ60の始端側にて軸方向と略直角に開口する残層用洗浄液供給口72aをなしている。ハブ41内において残層用洗浄液受け部46に対して半径方向に重なるフィードチューブ60の途中には、残層用洗浄液供給管72の開放口72bが軸方向と略直角に開口している。

[0064]

以上のような第3実施の形態によれば、残層用洗浄液受け部46に供給された洗浄液は、フライト42の処理物搬送面42aと反対側の面42bに隣接する位置にて、フライト42のらせん方向に沿って所定間隔おきに設けられている接続管47を通り、スクリューコンベヤ40のハブ41に設けられている残層用洗浄液排出孔48から飛び出す。

[0065]

ボウル20内に飛び出した洗浄液は飛び散ることなく、前記フライト42の反対側の面42bにおける外周縁に沿って取り付けられたカバーフライト50と、フライト42外周縁との間の細い隙間より、前記残層結晶に向けて直接噴出させることができる。

[0066]

ここで、洗浄液受け部43と残層用洗浄液受け部46とには、互いに仕切られた状態で別々に洗浄液が供給されるので、洗浄ノズル45から噴出させる洗浄液の液量と、カバーフライト50とフライト42外周縁との間の細い隙間から噴出させる洗浄液の液量とを、外部より別々にコントロールすることができるため、結晶洗浄の置換率および目漏れ量の低減を図るための両方の最適な洗浄液液量の調整を容易に行うことができる。

[0067]

図7および図8は本発明の第4実施の形態を示している。

本実施の形態に係る遠心分離機10Cでは、前記スクリューコンベヤ40のハブ41の一端側内部に、前記残層結晶を洗浄する洗浄液を受け入れる残層用洗浄液受け室54が、前記洗浄液受け部43とは別に区画して設けられている。本実施の形態では、残層用洗浄液受け室54はハブ41の最先端部分に設けられている。

[0068]

ハブ41の外周には、複数の残層用洗浄液導入管53が、それぞれ前記フライト42を貫通してハブ41の軸方向に延びる状態で、ハブ41の円周方向に所定間隔おきに配列するように取り付けられている。前記残層用洗浄液受け室54の底部には残層用洗浄液連通孔54aが穿設されており、各残層用洗浄液導入管53の一端側は、それぞれ残層用洗浄液連通孔54aを介して残層用洗浄液受け室54内に連通接続されている。

[0069]

各残層用洗浄液導入管 5 3 の他端側は閉じられているが、各残層用洗浄液導入管 5 3 の途中には、前記フライト 4 2 の反対側の面 4 2 b に隣接する位置にて、フライト 4 2 のらせん方向に沿って所定間隔おきに並ぶ複数の残層用洗浄液排出孔 5 3 a が設けられている。

[0070]

各残層用洗浄液排出孔 5 3 a から飛び出す残層用洗浄液受け室 5 4 の洗浄液は、前記カバーフライト 5 0 とフライト 4 2 外周縁との間の隙間より、前記残層結晶に対して直接噴出

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されるようになっている。なお、ハブ41内において残層用洗浄液受け室54に対して半径方向に重なるフィードチューブ60の途中には、残層用洗浄液供給管72の開放ロ72 bが軸方向と略直角に開口している。

[0071]

以上のような第4実施の形態によれば、残層用洗浄液受け室54に供給された洗浄液は、ハブ41の外周に配列されている複数の残層用洗浄液導入管53にそれぞれ導入される。そして、各残層用洗浄液導入管53内に導入された洗浄液は、各残層用洗浄液導入管53の途中に所定間隔おきに設けられている複数の残層用洗浄液排出孔53aを通り、ボウル20内に飛び出す。

[0072]

ボウル20内に飛び出した洗浄液は飛び散ることなく、前記フライト42の反対側の面4 2bにおける外周縁に沿って取り付けられたカバーフライト50と、フライト42外周縁 との間の細い隙間より、前記残層結晶に向けて直接噴出させることができる。それにより 、前記洗浄ノズル45による処理物の洗浄と、各残層用洗浄液導入管53による残層結晶 の洗浄を別々に行うことができ、それぞれの洗浄液の種類や液量を互いに異ならせること もできる。

[0073]

以上、本発明の実施の形態を図面によって説明してきたが、これらの具体的な構成によれば、結晶に対する洗浄液の透過性および残層結晶の移動性を高めることが可能となる。ただし、本発明はこれらの実施の形態に限定されるものではなく、本発明の要旨を逸脱しない範囲における変更や追加があっても本発明に含まれることは言うまでもない。

[0074]

【発明の効果】

本発明に係る遠心分離機によれば、スクリューコンベヤのフライト外周縁より、スクリーン部の内周面に付着している残層処理物に直接洗浄液を噴射させることができるため、この残層の移動性を改善し、洗浄液全体の透過性が増すため、局所的に残層処理物のみを洗浄し、処理物の含液率を高くすることにより、残層の固化防止が可能となる。

[0075]

また、スクリーン部の目漏れについても処理物全体に洗浄液をかけた場合、処理物層を通過する洗浄液の液量に比例した量の処理物と、スクリーン部の目開きに比例した量の処理物の目漏れを生じるが、前述の如く洗浄液をフライト外周縁より直接的に残層処理物に噴射することにより、残層処理物の固着がなくなり、搬送中の処理物に対する洗浄液の透過率が向上するため、本来の処理物中の不純物の置換用としての洗浄液量を抑制することが可能になり、スクリーン部における処理物の総合目漏れ量を減少させることが可能となる

【図面の簡単な説明】

- 【図1】本発明の第1実施の形態に係る遠心分離機の要部を示す縦断面図である。
- 【図2】本発明の第1実施の形態に係る遠心分離機の全体を示す縦断面図である。
- 【図3】図1のIII-III線断面図である。
- 【図4】本発明の第2実施の形態に係る遠心分離機の要部を示す縦断面図である。
- 【図5】本発明の第3実施の形態に係る遠心分離機の要部を示す縦断面図である。
- 【図6】図5のVI-VI線断面図である。
- 【図7】本発明の第4実施の形態に係る遠心分離機の要部を示す縦断面図である。
- 【図8】図7のVIII-VIII線断面図である。

【符号の説明】

- 10…遠心分離機
- 1 0 A … 遠心分離機
- 1 0 B … 遠心分離機
- 1000% 遠心分離機
- 11…ケーシング

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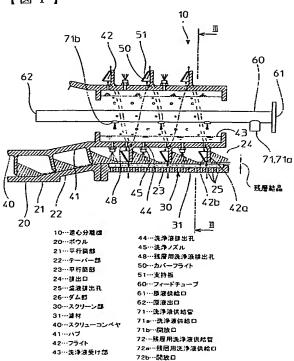
- 12a, 12b…シャフト
- 13…軸受け
- 1 4 … 差動装置
- 15…結晶排出口
- 16…洗浄液排出口
- 17…母液排出口
- 20…ボウル
- 21…平行简部
- 22…テーパー部
- 23…平行筒部
- 2 4 … 排出口
- 25…濾液排出孔
- 26…ダム部
- 30…スクリーン部
- 3 1 … 濾材
- 40…スクリューコンベヤ
- 41…ハブ
- 42…フライト
- 43…洗浄液受け部
- 4 3 a … 仕切り板
- 4 4 … 洗净液排出孔
- 4 5 … 洗浄ノズル
- 4 6 … 残層用洗浄液受け部
- 4 7 … 接続管
- 48 … 残層用洗浄液排出孔
- 50…カバーフライト
- 5 1 … 支持板
- 5 3 … 残層用洗浄液導入管
- 5 4 … 残層用洗浄液受け室
- 5 4 a … 残層用洗浄液連通孔
- 60…フィードチューブ
- 6 1 … 原液供給口
- 6 2 … 原液出口
- 7 1 … 洗净液供給管
- 7 1 a … 洗浄液供給口
- 7 1 b … 開放口
- 7 2 … 残層用洗浄液供給管
- 7 2 a … 残層用洗浄液供給口
- 7 2 b … 開放口
- 7 3 … 洗净液供給管
- 7 3 a … 洗净液供給口
- 7 3 b … 開放口

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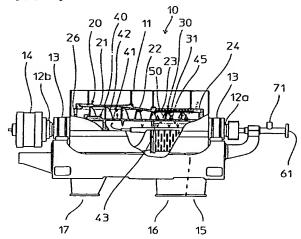
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【図1】

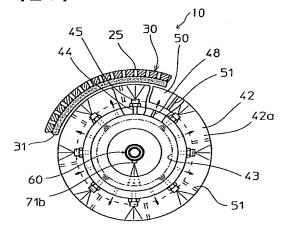


【図2】

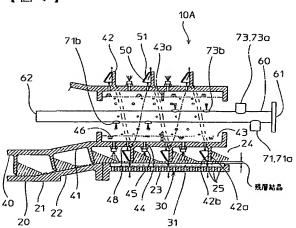


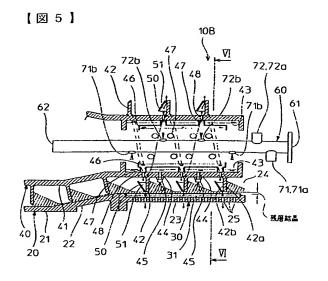
[図3]

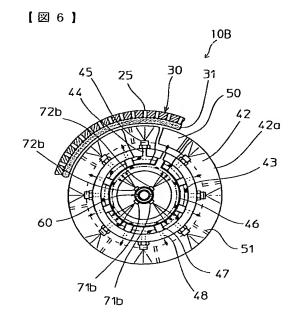
43…洗浄液受け部

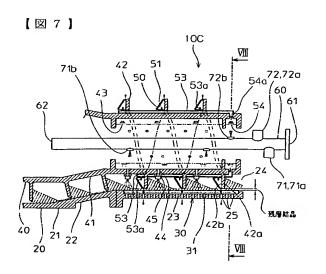


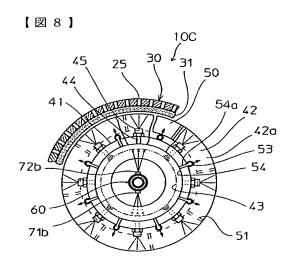
【図4】











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